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PATENT ABSTRACTS OF JAPAN

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(71) Applicant: POLA CHEM IND INC

(72) Inventor: TAKATSUKA ISAMU

(74) Representative:

(54) COSMETIC HAVING EXCELLENT MAKEUP DURABILITY

(57) Abstract:

PURPOSE: To provide the titled cosmetic having extremely high affinity to the human skin, hair, nail, etc., excellent water resistance, and resistant to the degradation of the makeup caused by sweat, tear, etc., by using an amino group-containing organopolysiloxane and an organic acid as essentialy components.

CONSTITUTION: A cosmetic composition excellent makeup durability, is prepared by compounding a cosmetic base with 1W50% of one or more amino group-containing organopolysiloxane having the siloxane unit of formula (Z is -NH2, NHR4NH2, or -OR4NH2; R1 and R4 are bivalent hydrocarbon group; R2 is univalent hydrocarbon group; R3 is OH or alkoxy; a and b are 0W2 provided that a+b= 0W2) and pref. liquid at

30°C, and pref. one or more organic acids such as dibasic acid, acidic amino acid, etc. The pH of the composition is pref. 5W9. Although the composition is pref. used in the form of emulsion, it can be used as a uniform aqueous solution. It does not exert uncomfortable feelings such as hot feeling, stretching feeling, etc., on the skin, and can be removed easily with a cleaning agent.

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$$\frac{R_a^2}{2 - R^1 - S_{i0}^3 - a - b}$$